

US DEPARTMENT OF COMMERCE
PATENT AND TRADEMARK OFFICE

APPLICANT: MARTIN RICHARDSON

FOR: EUV, XUV, AND X-RAY WAVELENGTH SOURCES CREATED FROM LASER PLASMA
PRODUCED FROM LIQUID METAL SOLUTIONS, AND NANO-SIZE PARTICLES IN SOLUTIONS

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EXAMINER	DOCUMENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
CT	AA 4,024,400	05/17/77	Blytas et al.	250	432	05/13/76
	AB 4,328,464	05/04/82	Pivirotto	330	4.3	02/07/80
	AC 4,700,371	10/13/87	Forsyth et al.	378	34	11/08/84
	AD 4,723,262	02/02/88	Noda et al.	378	119	12/26/85
	AE 4,866,517	09/12/89	Mochizuke et al.	378	119	09/10/87
	AF 4,953,191	08/28/90	Smither et al.	378	143	07/24/89
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Courtney Thomas 01.02.03